KINTEK SOLUTION

Pacvd Catalog

Contact us for more catalogs of Sample Preparation, Thermal Equipment, Lab Consumables & Materials, Bio-Chem Equipment, etc...

KINTEK SOLUTION

COMPANY PROFILE

>>> About Us

Kintek Solution Ltd is one technology orientated organization, team members are devoted to probing the most efficicent and reliable technology and innovations in the scienticfic researching equipment, fields like biochemical reacting, new materials researching, heat treatment, vaccum creating, refrigerating, as while as pharmaceutical and petroleum extracting equipment.

In the past 20 years, we earned rich experiences in this researing equipment field, we are capable to supply both the equipment and solution according to customer’s needs and realities, we have also developed lots of customer tailer equipment accoding to a specific working purpose, and we have lots of successful projects in many universities and institutes from different countries, like Asia,Europe,North and south America, Australia and New Zealand, middle east, and Africa.

Profession, quick response, hard working, and sincerity is a remarkable label of our team meambers working attitude, which earn us a sound reputation among our clients.

We are here and ready to service our clients from different countries and regions, and share the most efficent and reliable technology together!

Slide Pecvd Tube Furnace With Liquid Gasifier Pecvd Machine

Item Number: KT-PE12

Introduction

KT-PE12 Slide PECVD System: Wide power range, programmable temp control, fast heating/cooling with sliding system, MFC mass flow control & vacuum pump.

Learn More

Furnace model	KT-PE12-60
Max. temperature	1200℃
Constant work temperature	1100℃
Furnace tube material	High purity quartz
Furnace tube diameter	60mm
Heating zone length	1x450mm
Chamber material	Japan alumina fiber
Heating element	Cr2Al2Mo2 wire coil
Heating rate	0-20℃/min
Thermal couple	Build in K type
Temperature controller	Digital PID controller/Touch screen PID controller
Temperature control accuracy	±1℃
Sliding distance	600mm
RF Plasma unit	
Output Power	5 -500W adjustable with ± 1% stability
RF frequency	13.56 MHz ±0.005% stability
Reflection Power	350W max.
Matching	Automatic
Noise	<50 dB
Cooling	Air cooling.
Gas precise control unit	
Flow meter	MFC mass flow meter
Gas channels	4 channels
Flow rate	MFC1: 0-5SCCM O2 MFC2: 0-20SCMCH4 MFC3: 0- 100SCCM H2 MFC4: 0-500 SCCM N2
Linearity	±0.5% F.S.

Repeatability	±0.2% F.S.
Pipe line and valve	Stainless steel
Maximum Operating Pressure	0.45MPa
Flow meter controller	Digital Knob controller/Touch screen controller
Standard vacuum unit(Optional)	
Vacuum pump	Rotary vane vacuum pump
Pump flow rate	4L/S
Vacuum suction port	KF25
Vacuum gauge	Pirani/Resistance silicon vacuum gauge
Rated vacuum pressure	10Pa
High vacuum unit(Optional)	
Vacuum pump	Rotary vane pump+Molecular pump
Pump flow rate	4L/S+110L/S
Vacuum suction port	KF25
Vacuum gauge	Compound vacuum gauge
Rated vacuum pressure	6x10-5Pa
Above specifications and setups can be customized	

No.	Description	Quantity
1	Furnace	1
2	Quartz tube	1
3	Vacuum flange	2
4	Tube thermal block	2
5	Tube thermal block hook	1
6	Heat resistant glove	1
7	RF plasma source	1
8	Precise gas control	1
9	Vacuum unit	1
10	Operation manual	1

Inclined Rotary Plasma Enhanced Chemical Deposition (Pecvd) Tube Furnace Machine

Item Number: KT-PE16

Introduction

Introducing our inclined rotary PECVD furnace for precise thin film deposition. Enjoy automatic matching source, PID programmable temperature control, and high accuracy MFC mass flowmeter control. Built-in safety features for peace of mind.

Learn More

Furnace model	PE-1600-60
Max. temperature	1600℃
Constant work temperature	1550℃
Furnace tube material	High purity Al2O3 tube
Furnace tube diameter	60mm
Heating zone length	2x300mm
Chamber material	Japan alumina fiber
Heating element	Molybdenum Disilicide
Heating rate	0-10℃/min
Thermal couple	B type
Temperature controller	Digital PID controller/Touch screen PID controller
Temperature control accuracy	±1℃
RF Plasma unit	
Output Power	5 -500W adjustable with ± 1% stability
RF frequency	13.56 MHz ±0.005% stability
Reflection Power	350W max.
Matching	Automatic
Noise	<50 dB
Cooling	Air cooling.
Gas precise control unit	
Flow meter	MFC mass flow meter
Gas channels	4 channels
Flow rate	MFC1: 0-5SCCM O2 MFC2: 0-20SCMCH4 MFC3: 0- 100SCCM H2 MFC4: 0-500 SCCM N2
Linearity	±0.5% F.S.

Repeatability	±0.2% F.S.
Pipe line and valve	Stainless steel
Maximum Operating Pressure	0.45MPa
Flow meter controller	Digital Knob controller/Touch screen controller
Standard vacuum unit(Optional)	
Vacuum pump	Rotary vane vacuum pump
Pump flow rate	4L/S
Vacuum suction port	KF25
Vacuum gauge	Pirani/Resistance silicon vacuum gauge
Rated vacuum pressure	10Pa
High vacuum unit(Optional)	
Vacuum pump	Rotary vane pump+Molecular pump
Pump flow rate	4L/S+110L/S
Vacuum suction port	KF25
Vacuum gauge	Compound vacuum gauge
Rated vacuum pressure	6x10-5Pa
Above specifications and setups can be customized	

No.	Description	Quantity
1	Furnace	1
2	Quartz tube	1
3	Vacuum flange	2
4	Tube thermal block	2
5	Tube thermal block hook	1
6	Heat resistant glove	1
7	RF plasma source	1
8	Precise gas control	1
9	Vacuum unit	1
10	Operation manual	1

Plasma Enhanced Evaporation Deposition Pecvd Coating Machine

Item Number: KT-PED

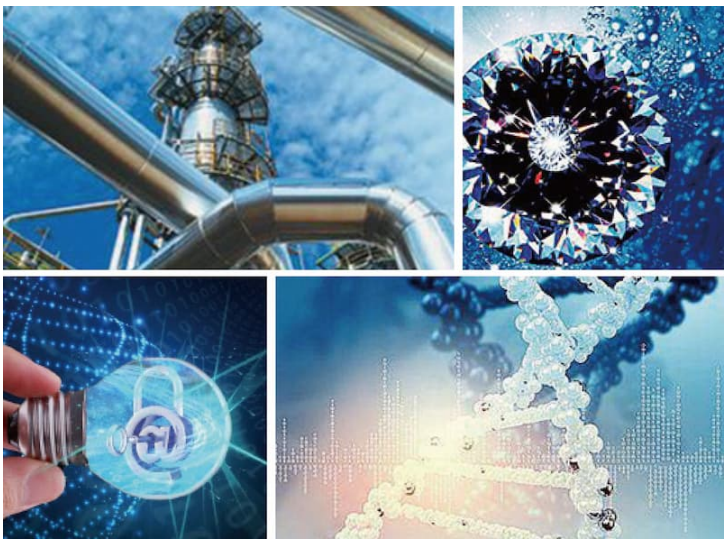
Introduction

Upgrade your coating process with PECVD coating equipment. Ideal for LED, power semiconductors, MEMS and more. Deposits high-quality solid films at low temps.

Learn More

Sample holder	Size	1-6 inches
	Rotate speed	0-20rpm adjustable
	Heating temperature	≤800℃
	Control accuracy	±0.5℃ SHIMADEN PID Controller
Gas purge	Flow meter	MASS FLOWMETER CONTROLLER (MFC)
	Channels	4 channels
	Cooling method	Circulating water cooling
Vacuum chamber	Chamber size	Φ500mm X 550mm
	Observation port	Full view port with baffle
	Chamber material	316 Stainless steel
	Door type	Front open type door
	Cap material	304 Stainless steel
	Vacuum pump port	CF200 flange
	Gas inlet port	φ6 VCR connector
Plasma power	Source power	DC power or RF power
	Coupling mode	Inductively coupled or plate capacitive
	Output power	500W—1000W
	Bias power	500v
Vacuum pump	Pre- pump	15L/S Vane vacuum pump
	Turbo pump port	CF150/CF200 620L/S-1600L/S
	Relief port	KF25
	Pump speed	Vane pump:15L/s□Turbo pump:1200l/s□1600l/s
	Vacuum degree	≤5×10-5Pa
	Vacuum sensor	Ionization/resistance vacuum gauge/film gauge
System	Electric power supply	AC 220V /380 50Hz

Rated power	5kW
Dimensions	900mm X 820mm X870mm
Weight	200kg



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